

FIG. 1a

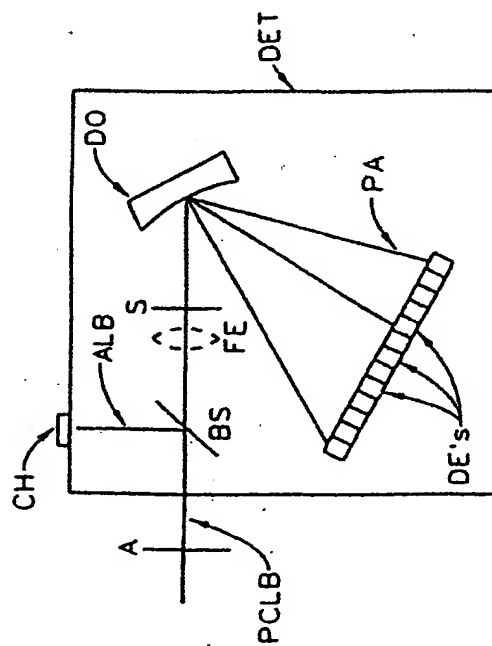


FIG. 2

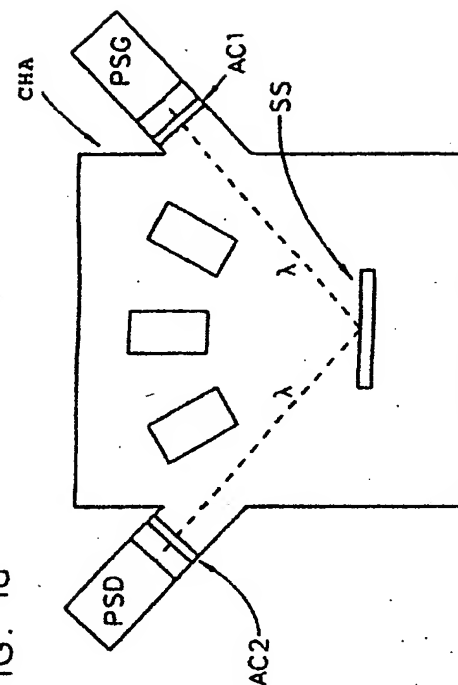


FIG. 1c

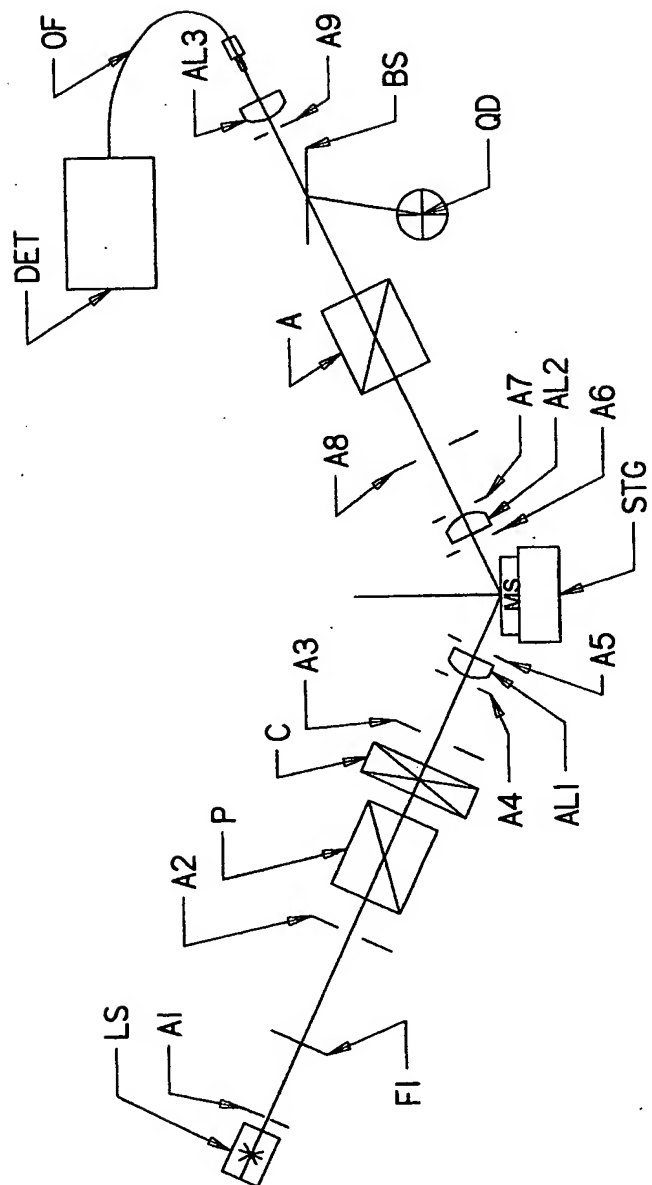


FIG. 1b

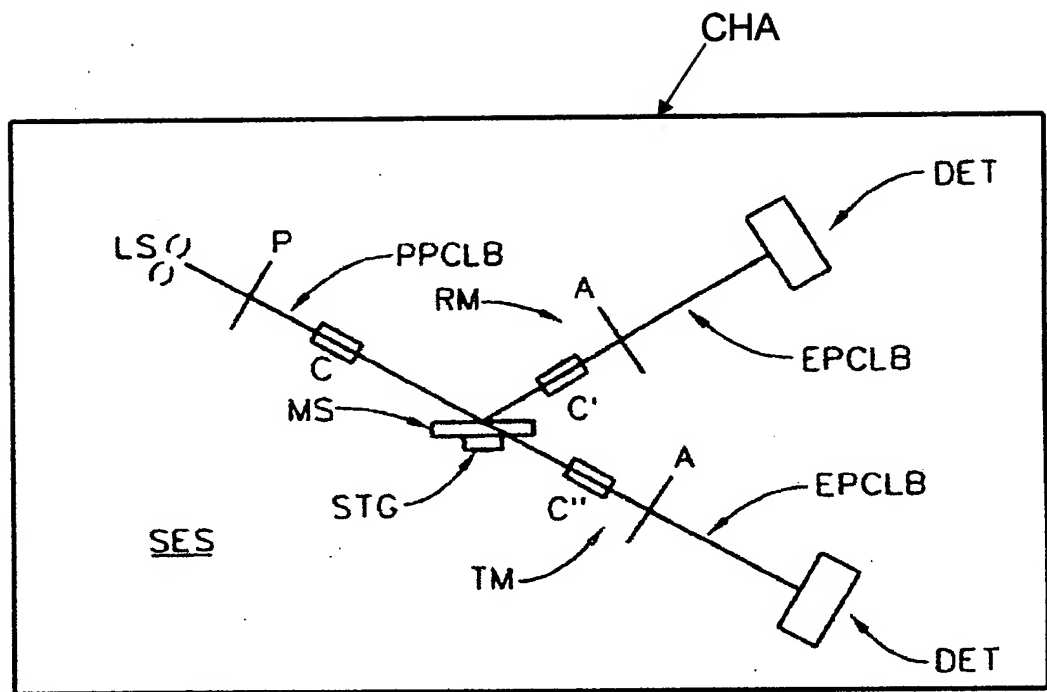


FIG. 1d

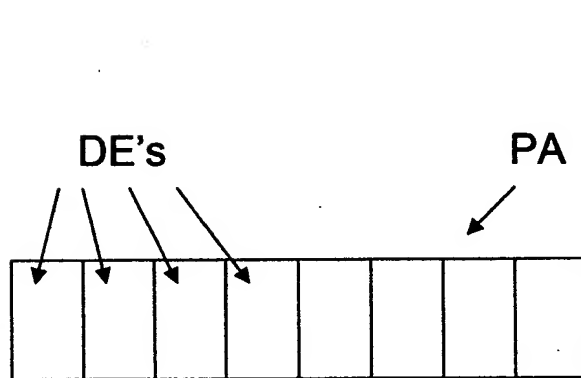


FIG. 1e

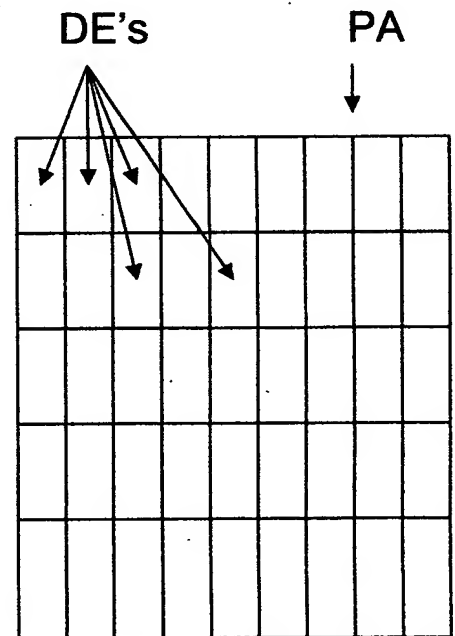


FIG. 1f

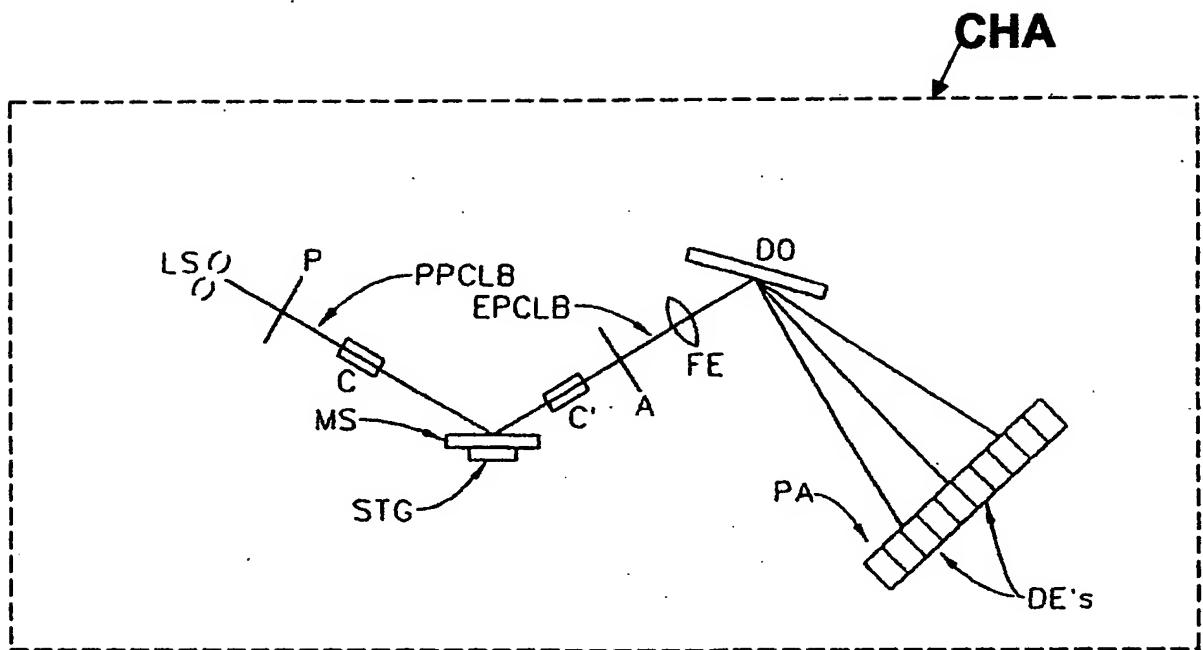


FIG. 3

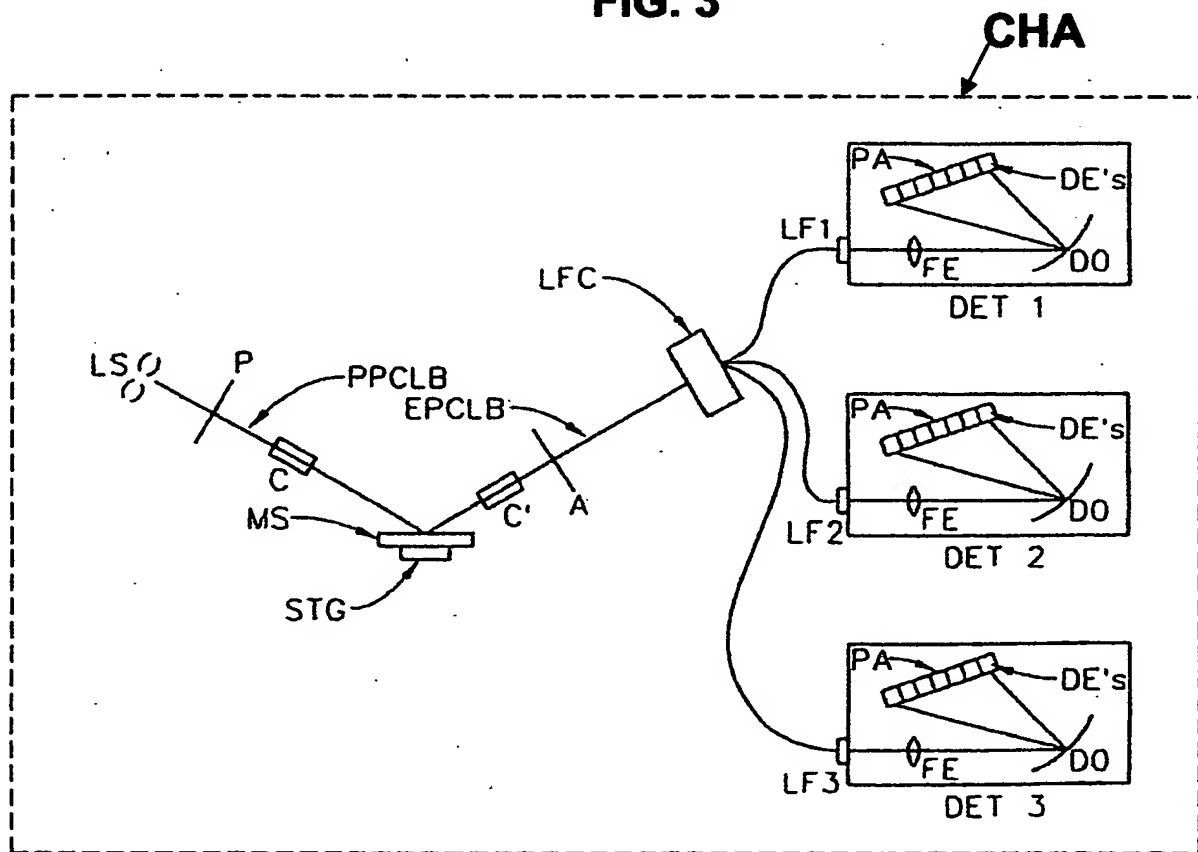


FIG. 4

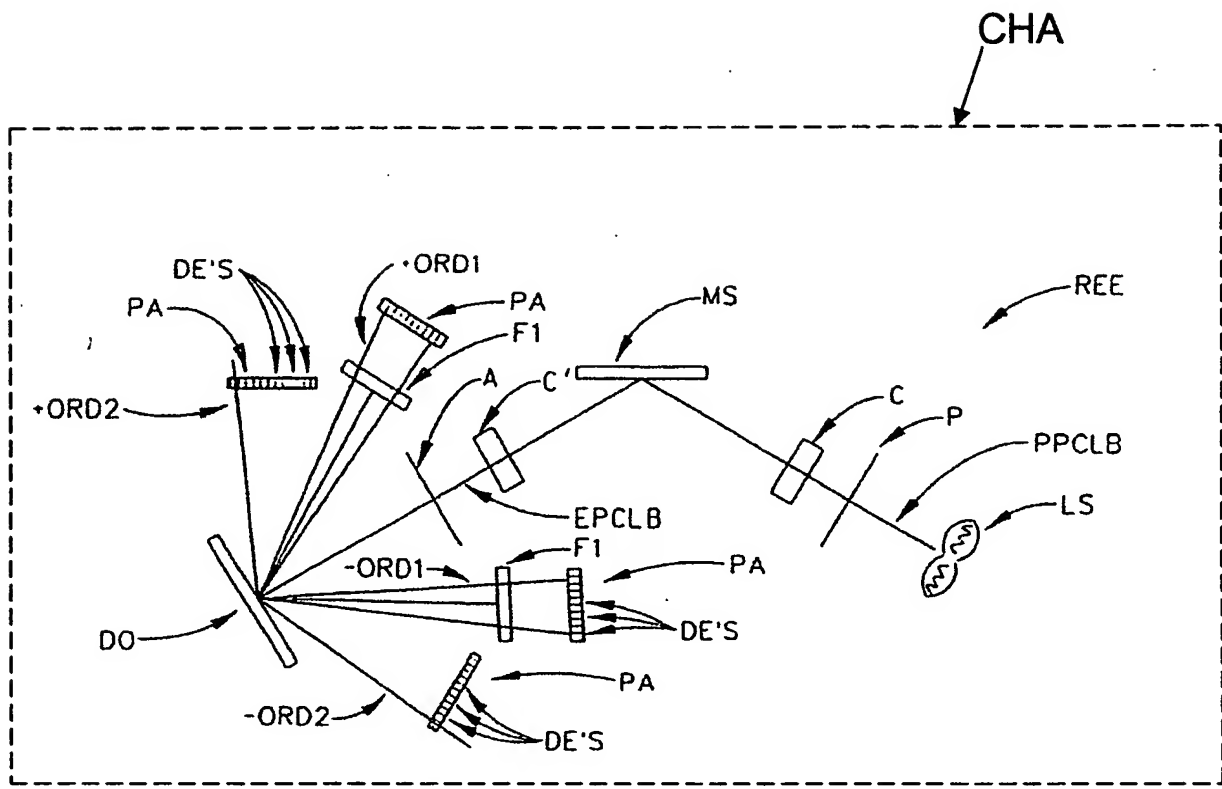


FIG 5a

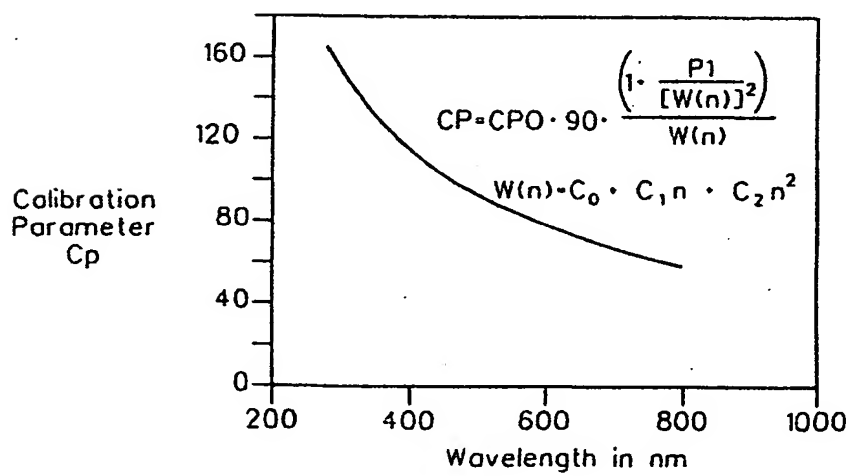


FIG. 6

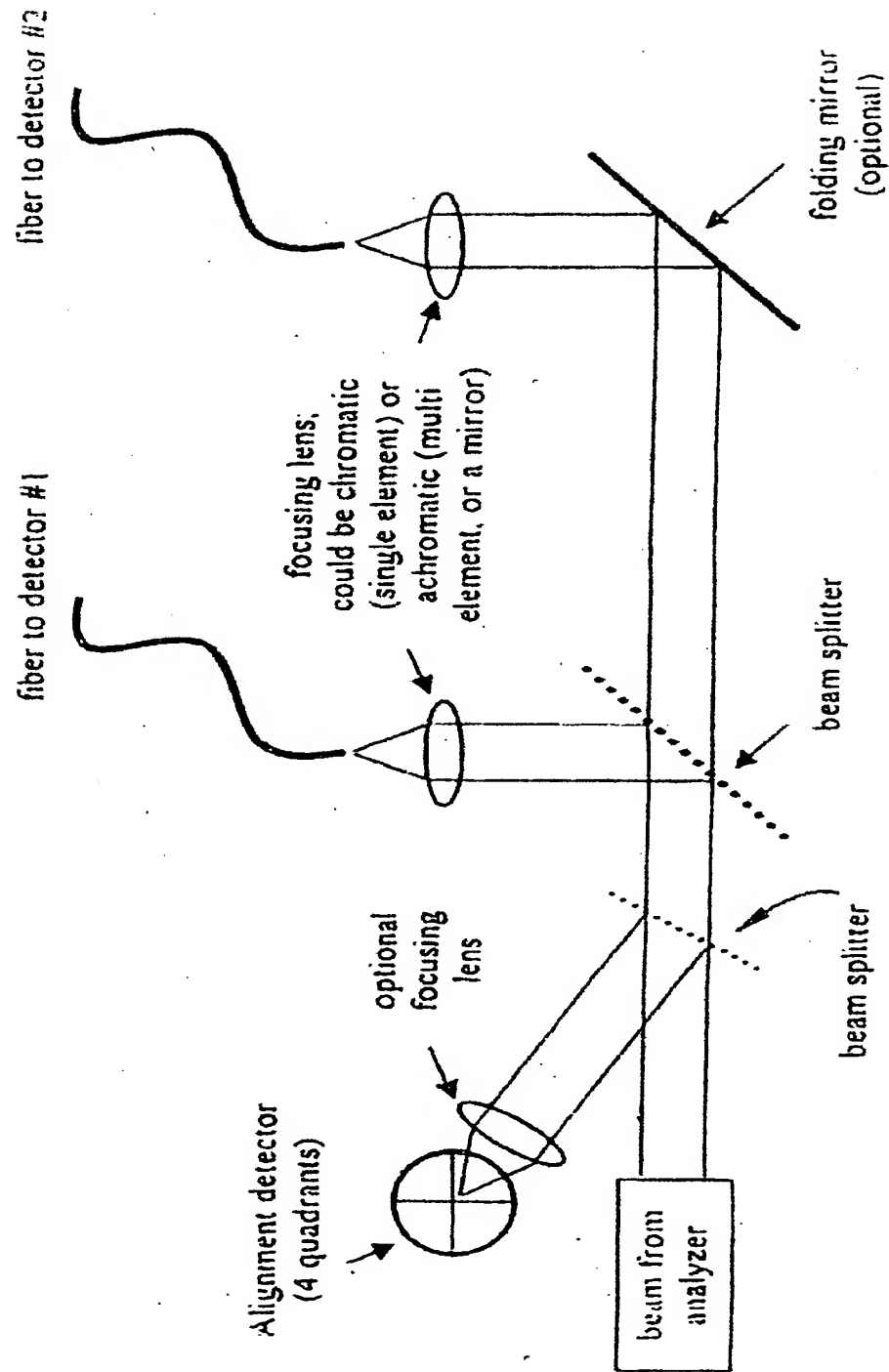


FIG 5b

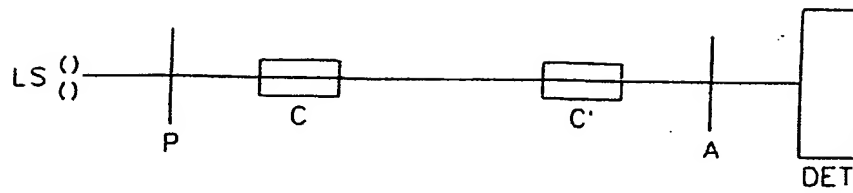


FIG. 7

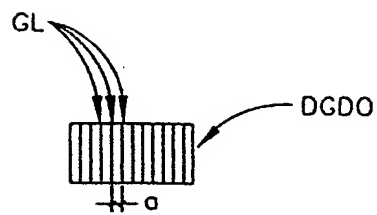


FIG. 8a

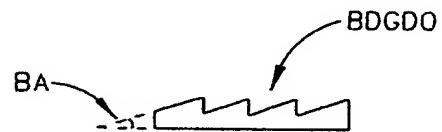


FIG. 8b

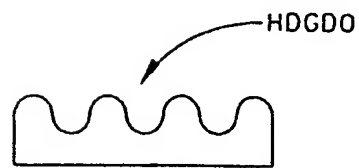


FIG. 8c

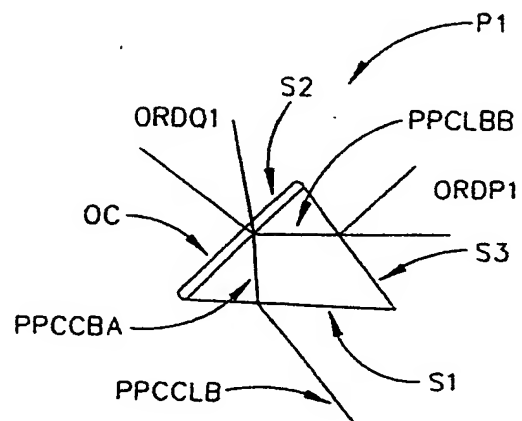


FIG. 8d

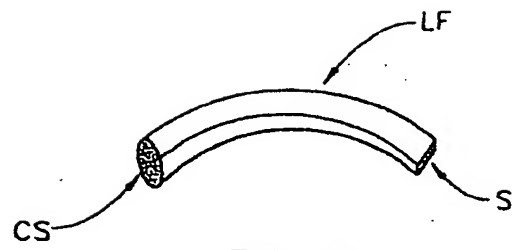


FIG. 9a

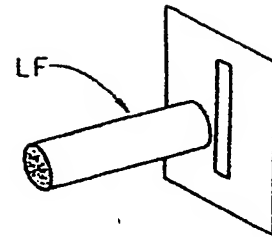


FIG. 9b

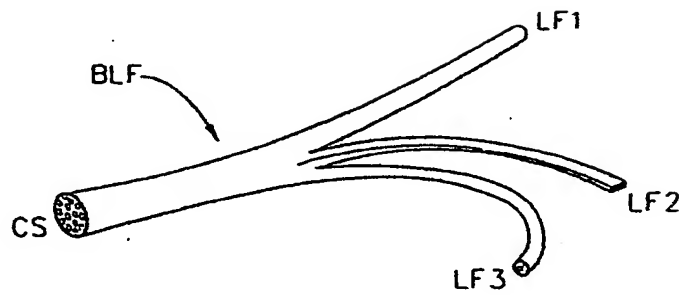


FIG. 9c

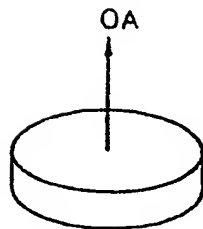


FIG. 9d



FIG. 9e

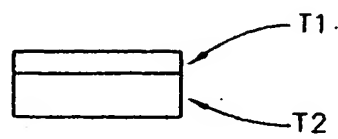


FIG 9f

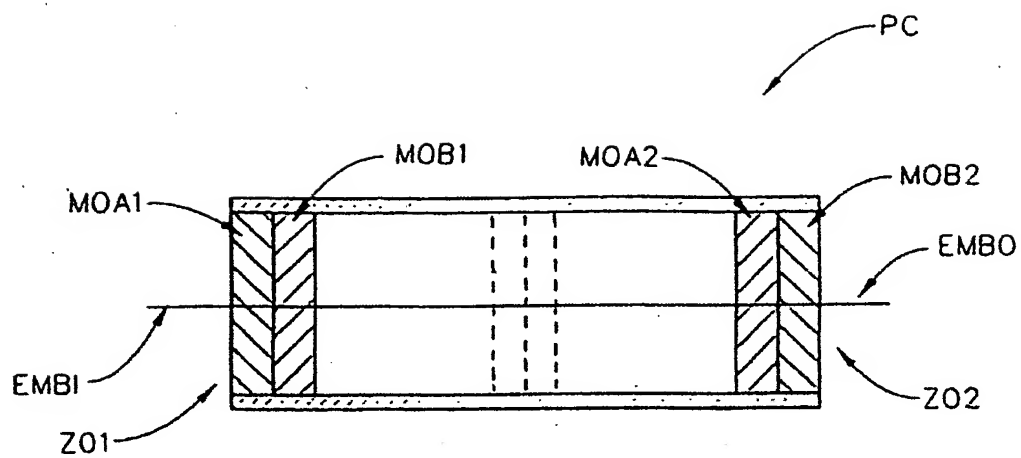


FIG. 9g₁



FIG. 9g₂

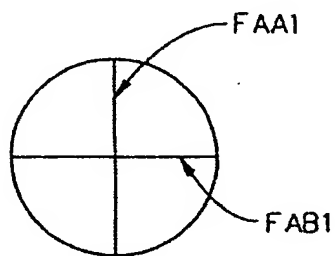


FIG. 9h

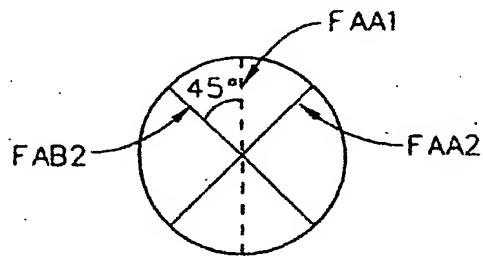


FIG. 9i

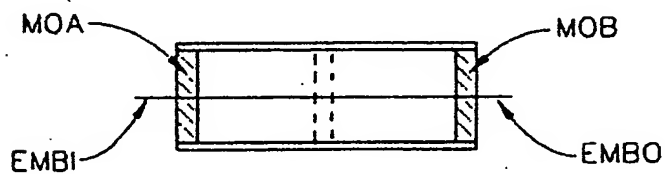


FIG. 9j

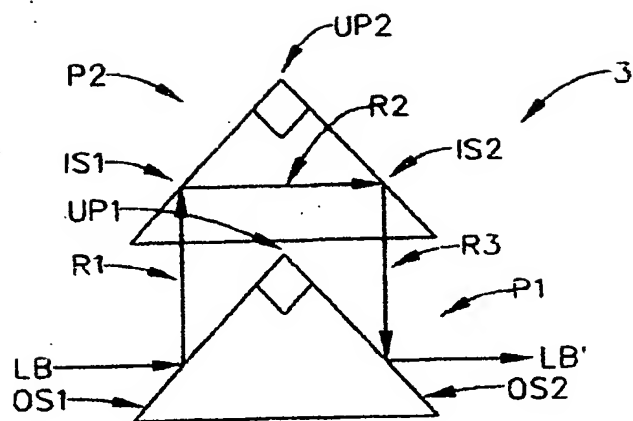


FIG. 9k1

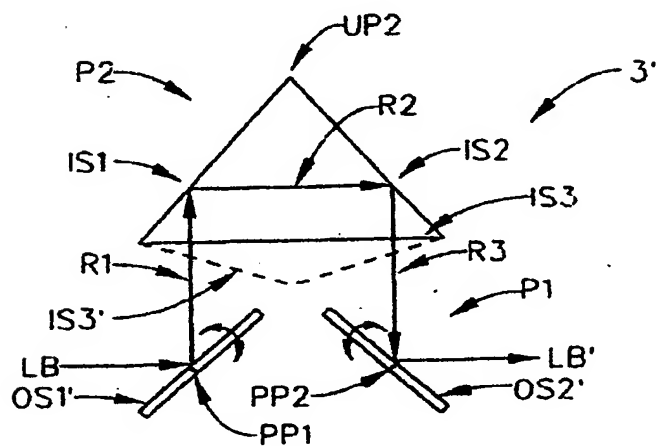


FIG. 9k2

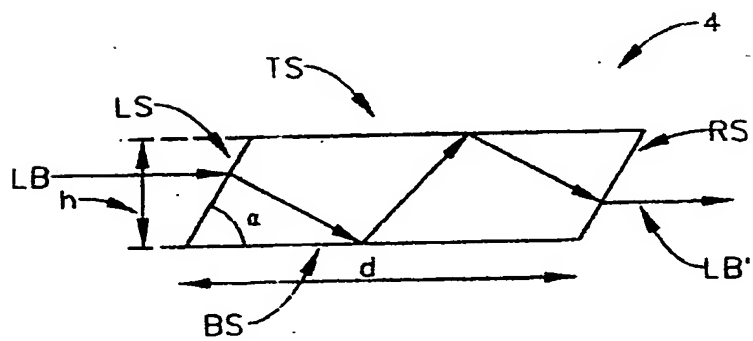


FIG. 9l

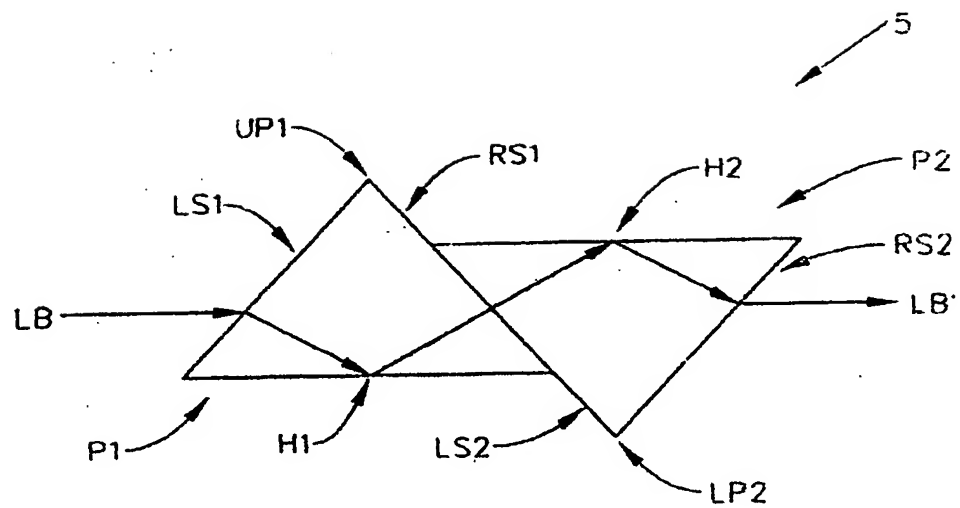


FIG. 9m

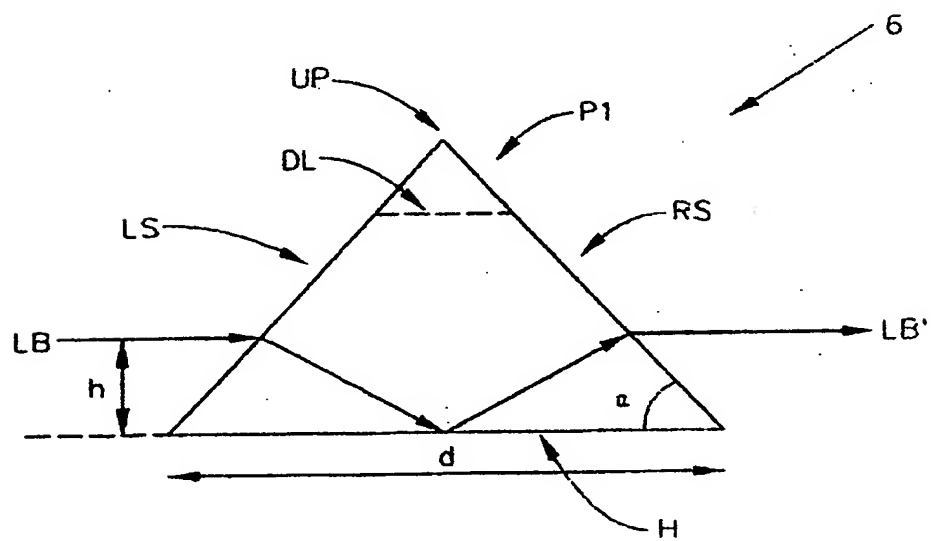


FIG. 9n

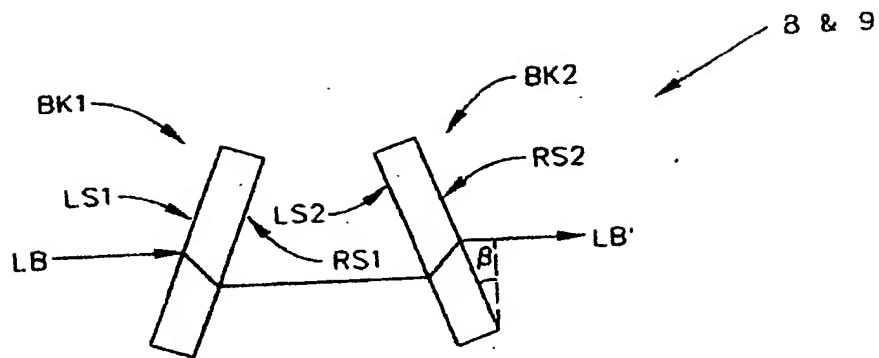


FIG. 9o1

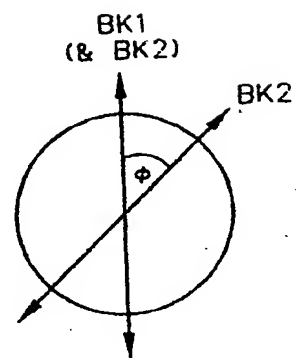


FIG. 9o2

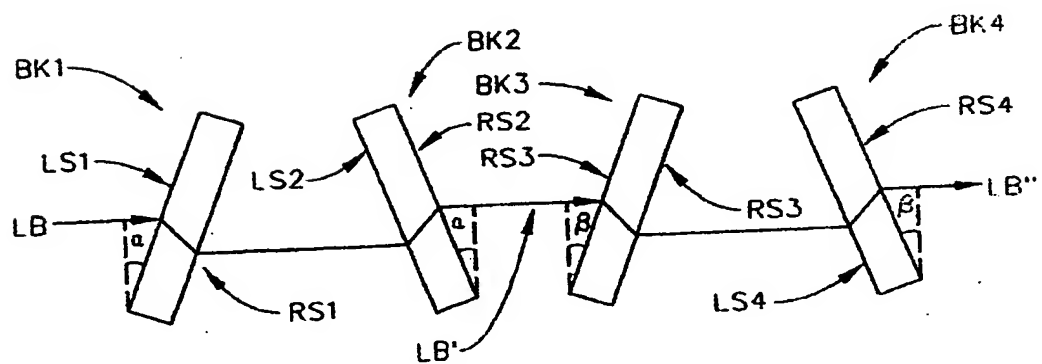


FIG. 9p1

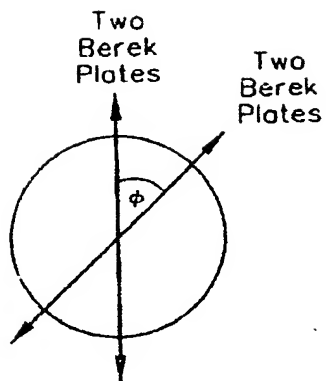


FIG. 9p2

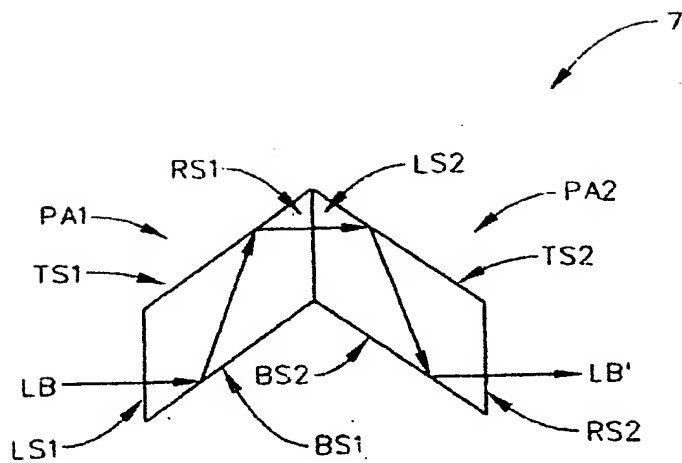


FIG. 9q

COMPARISON OF SINGLE VS. DUAL
WAVEPLATE COMPENSATOR DESIGN

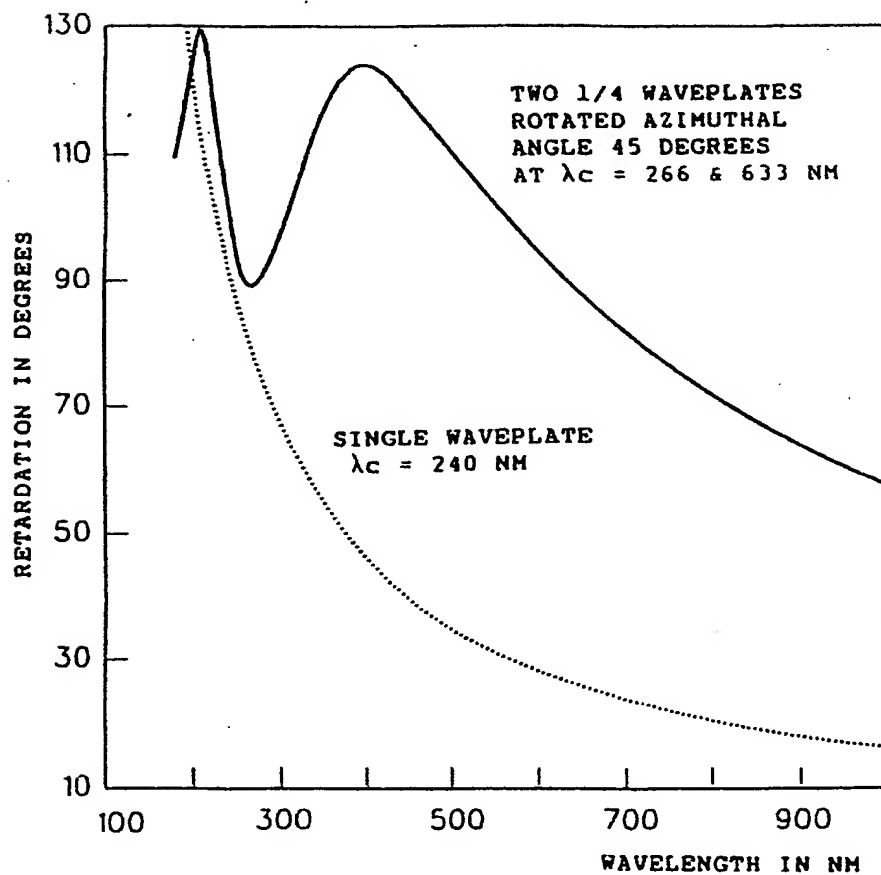


FIG. 10a

RETARDANCE CHARACTERISTICS OF WAVEPLATES
USED IN DUAL ELEMENT COMPENSATOR DESIGN

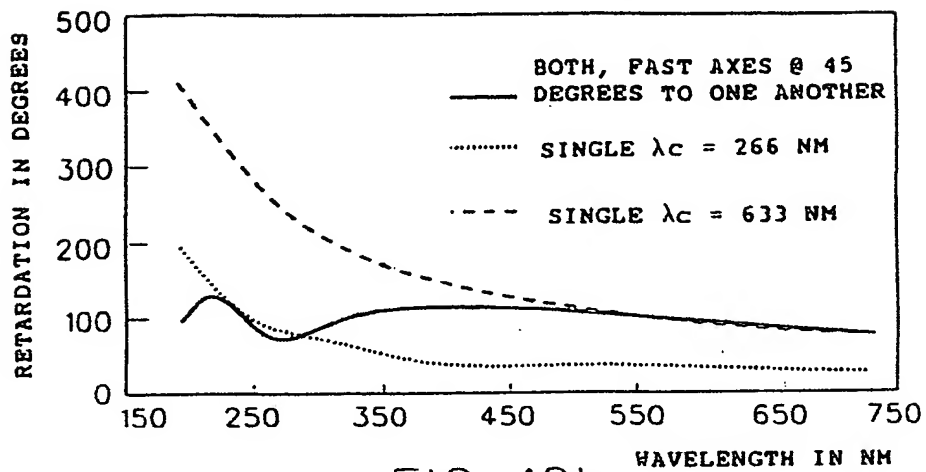


FIG. 10b

PRESENT INVENTION DUAL ELEMENT DESIGN
FOR $\lambda_c = 266, 633$ NM & $\phi = 45$ DEGREES

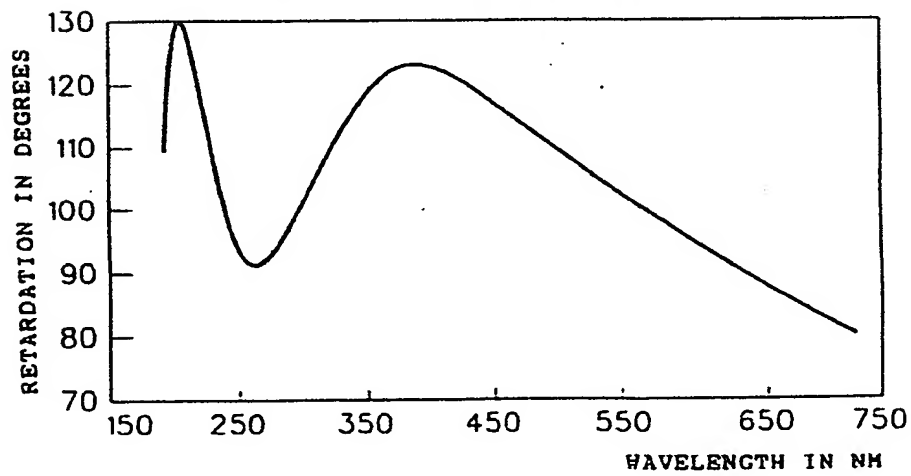


FIG. 10c

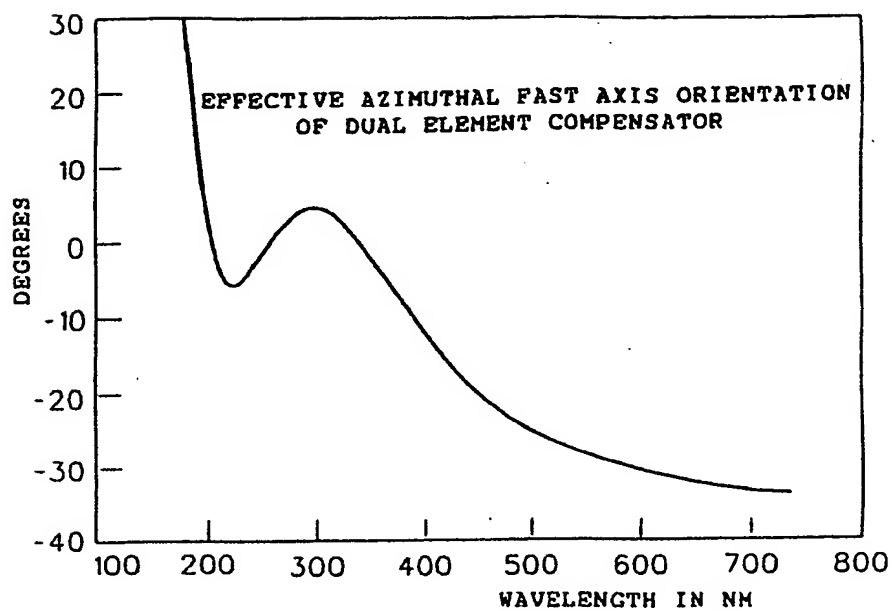


FIG. 10d

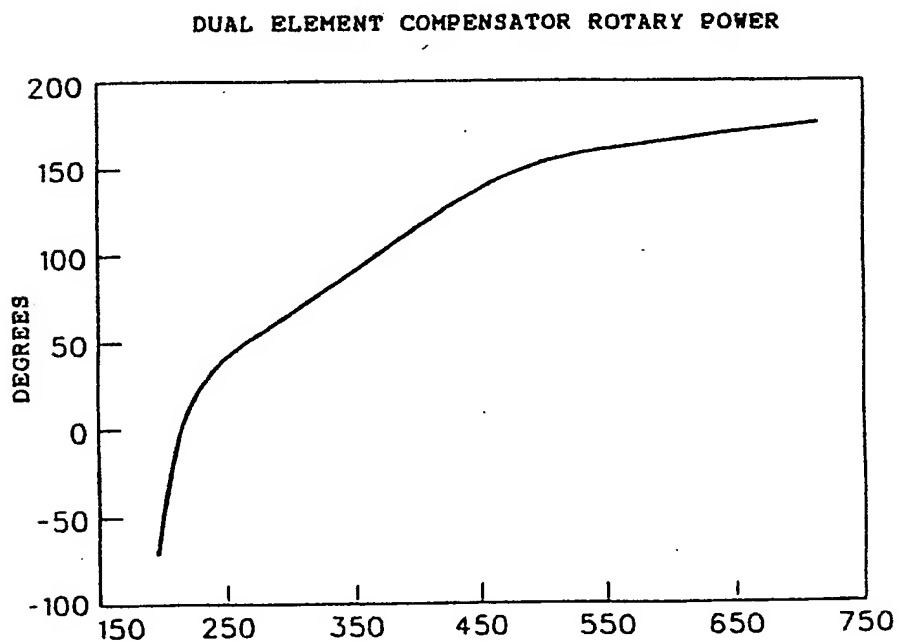


FIG. 10e

DUAL ELEMENT COMPENSATOR DESIGN FOR
UV-VIS SPECTRAL RANGE 245-850 NM

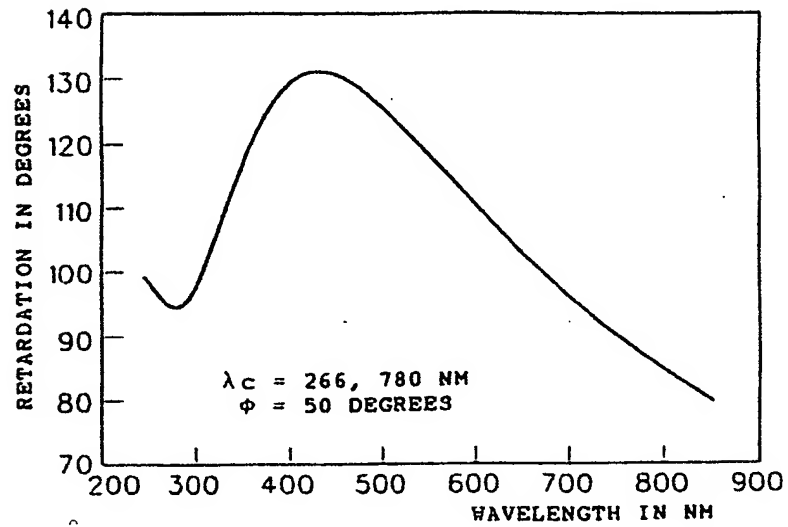


FIG. 10f

DUAL ELEMENT COMPENSATOR DESIGN FOR
UV-VIS SPECTRAL RANGE 390-1700 NM

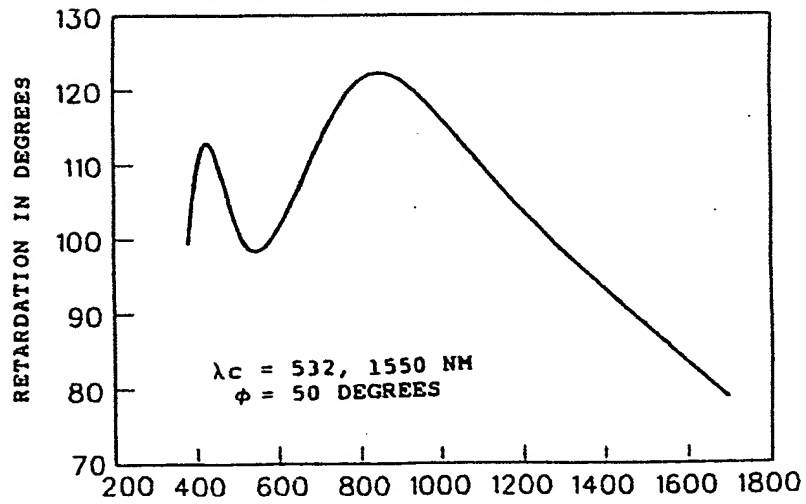


FIG. 10g₁

3-Element Compensator Design

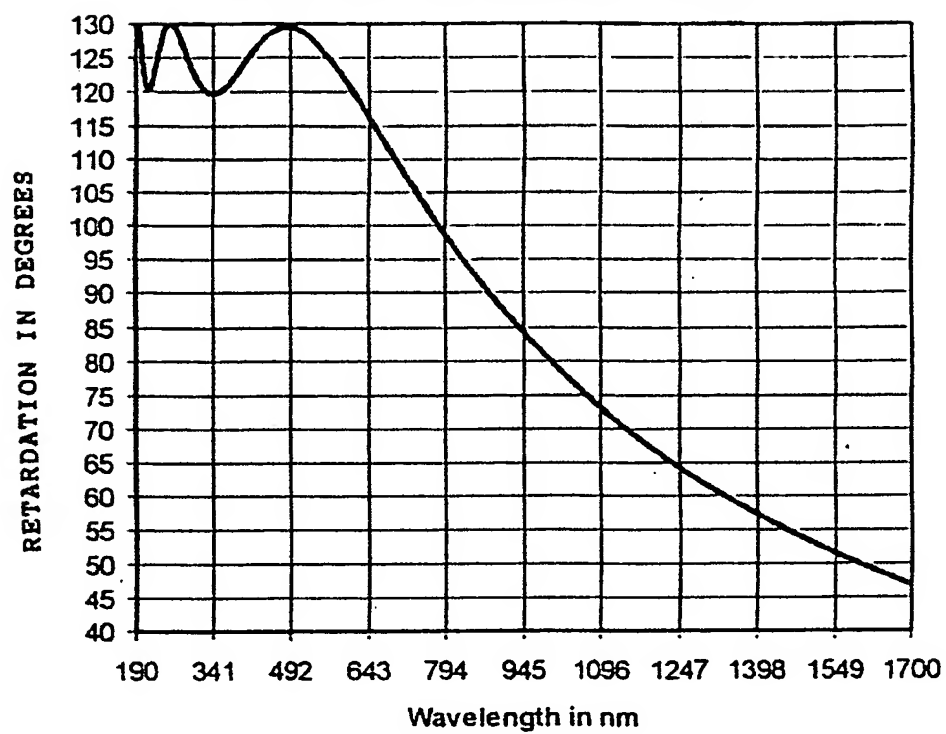


FIG. 10g 2

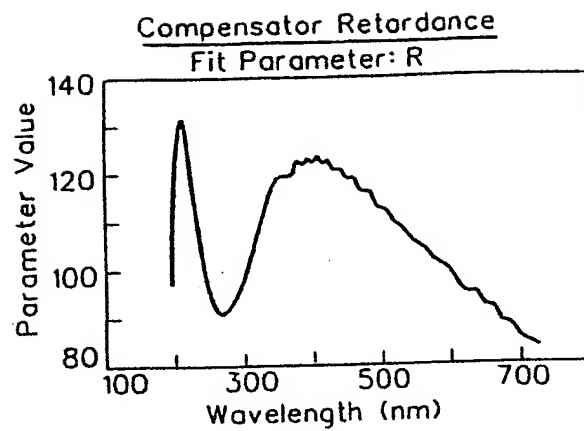


FIG. 10h

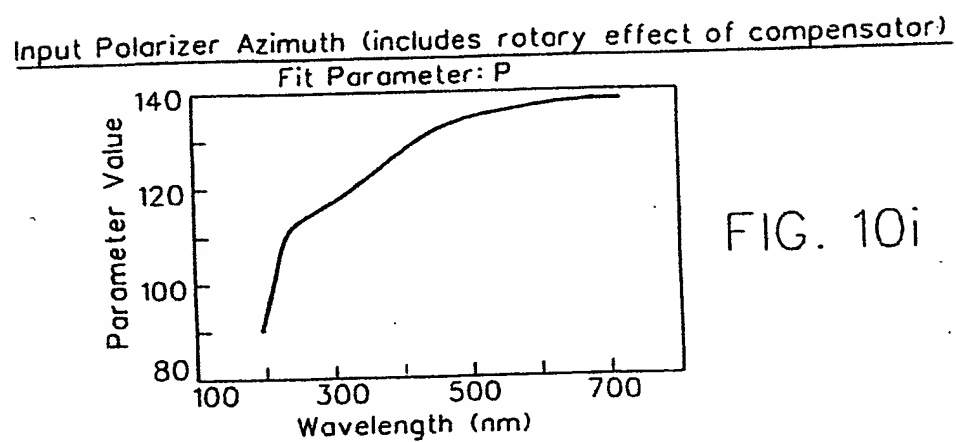


FIG. 10i

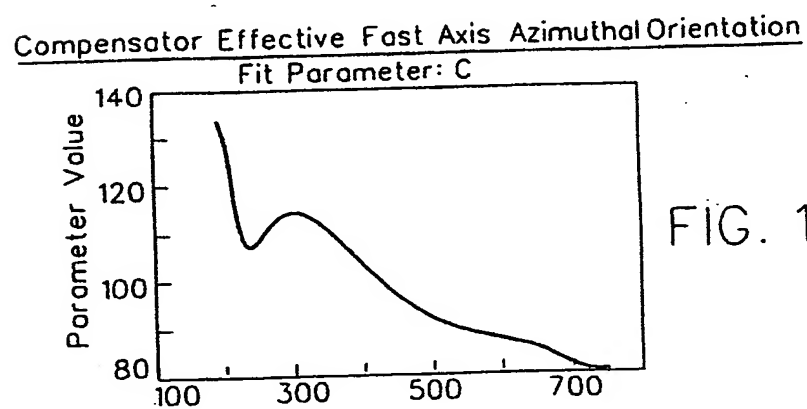


FIG. 10j

Depolarization Parameter 'C'

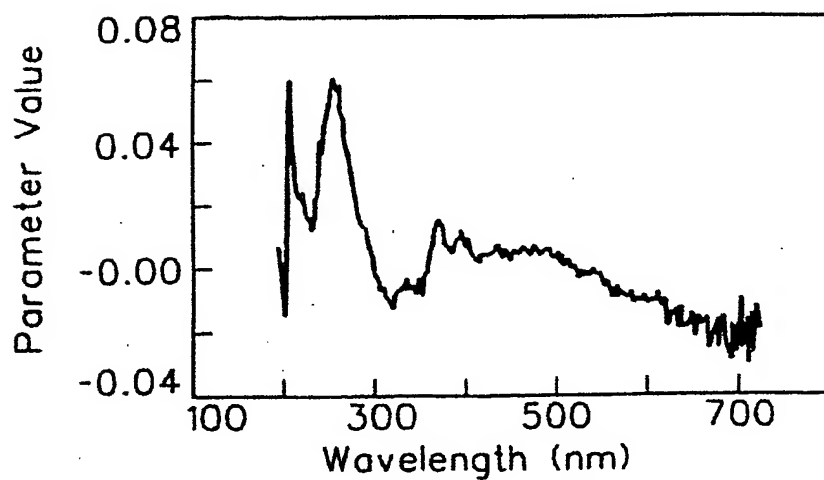


FIG. 10k

Depolarization Parameter 'B'

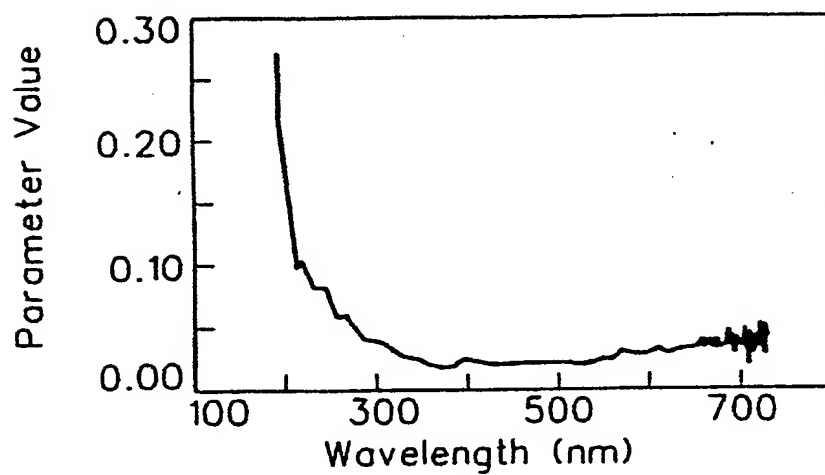
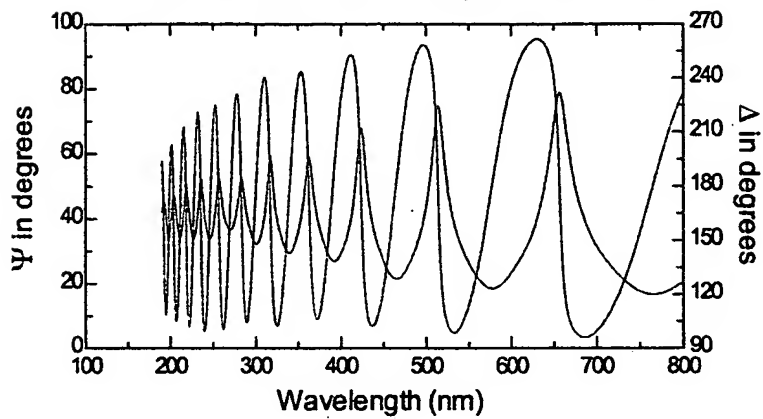


FIG. 10l

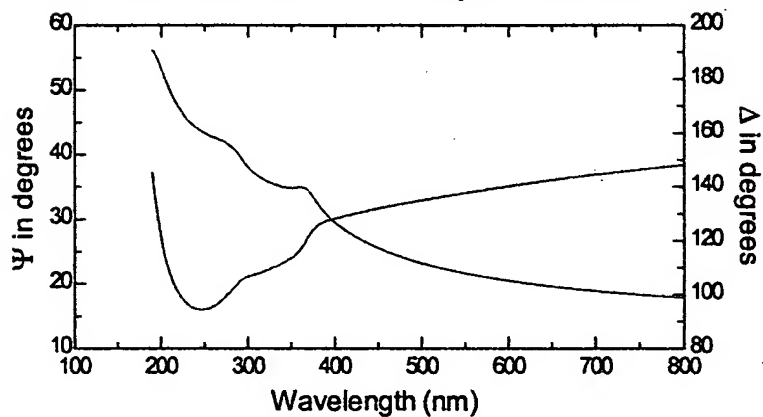
1 μ m Thick SiO₂ Film on Si
Generated and Experimental



— Model Fit
- - - Exp Ψ E65°
— Model Fit
- - - Exp Δ E65°

FIG. 10m

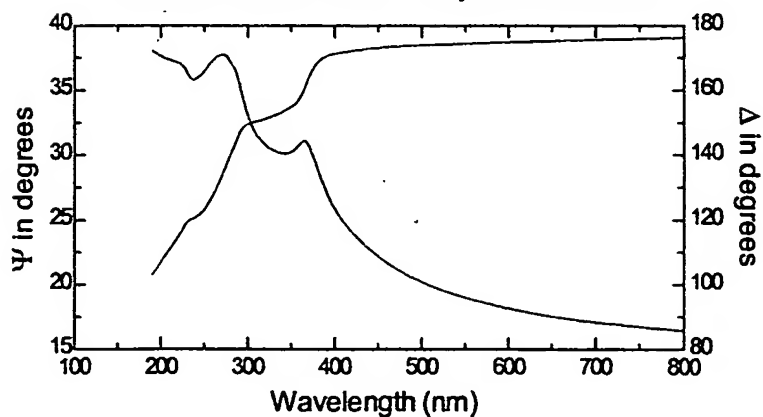
250Å Thick SiO₂ Film on Si
Generated and Experimental



— Model Fit
- - - Exp Ψ E65.2°
— Model Fit
- - - Exp Δ E65.2°

FIG. 10n

Native (25Å) SiO₂ Film on Si
Generated and Experimental



— Model Fit
- - - Exp Ψ E65.1°
— Model Fit
- - - Exp Δ E65.1°

FIG. 10o

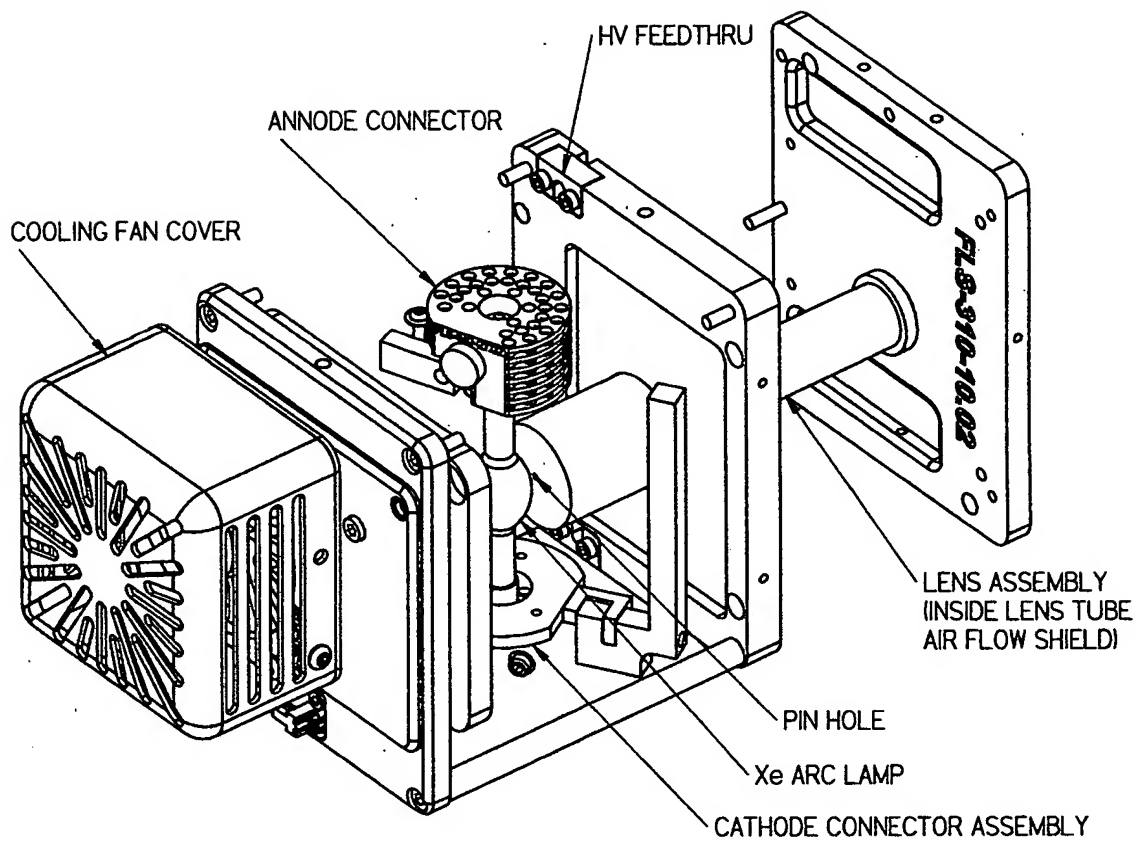


FIG. 11a

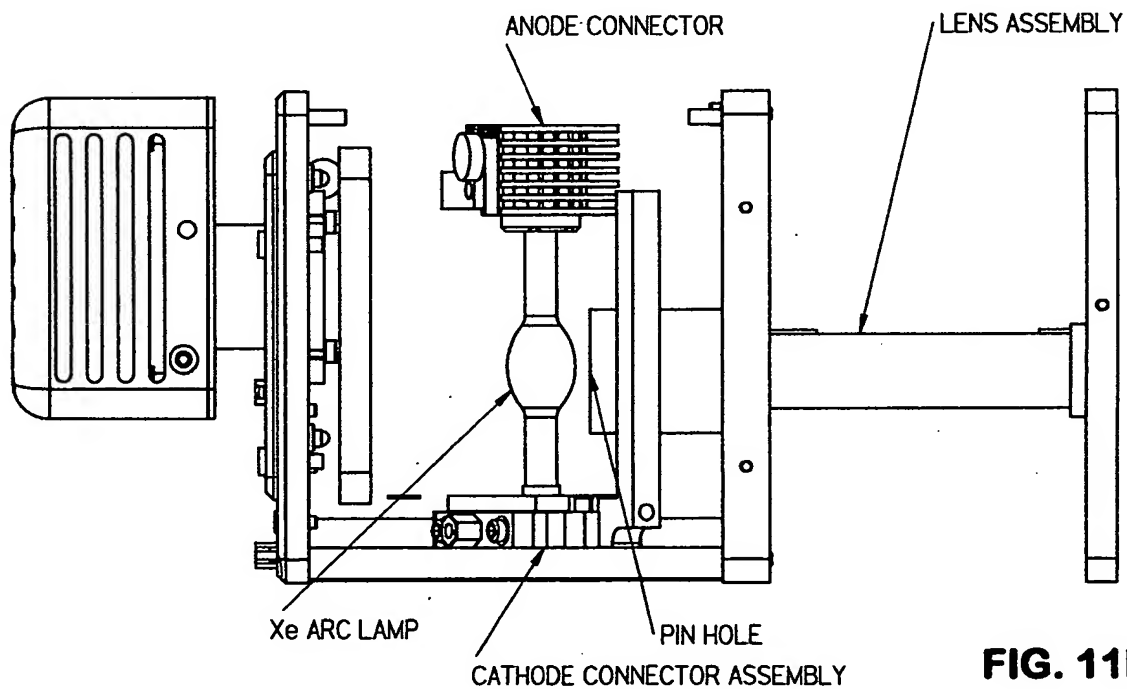


FIG. 11b

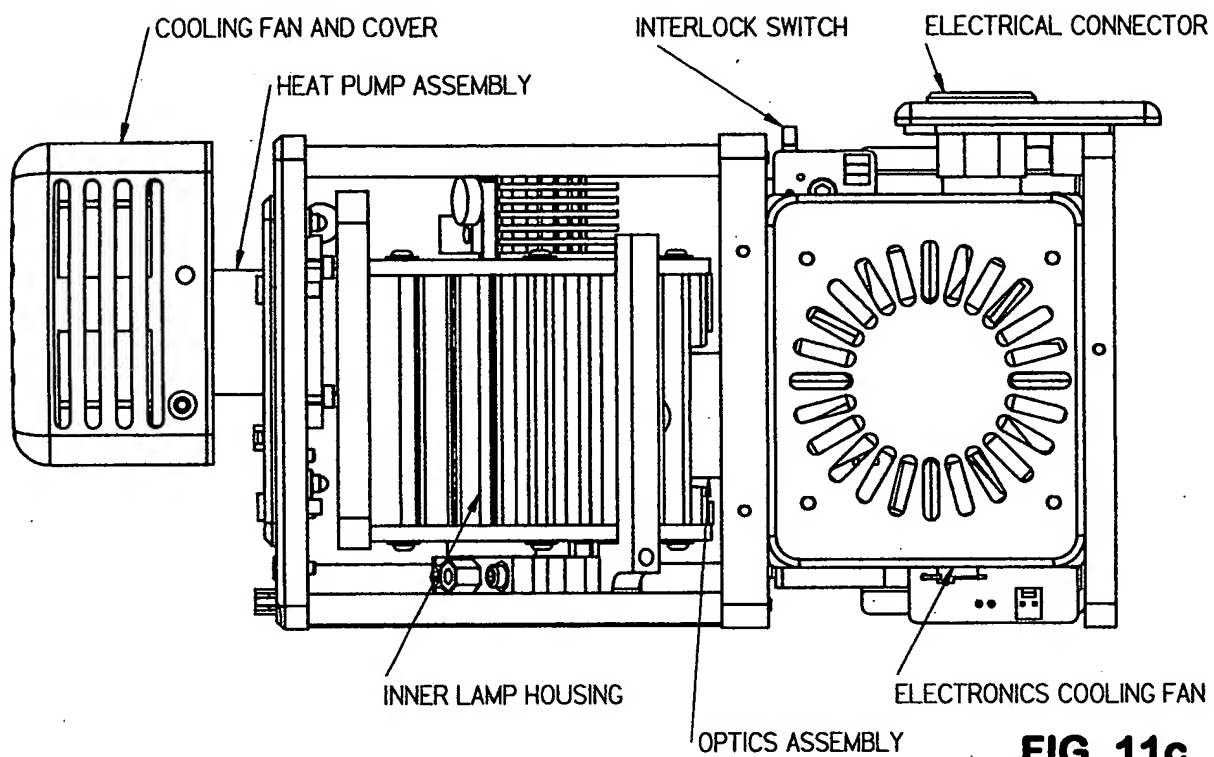


FIG. 11c

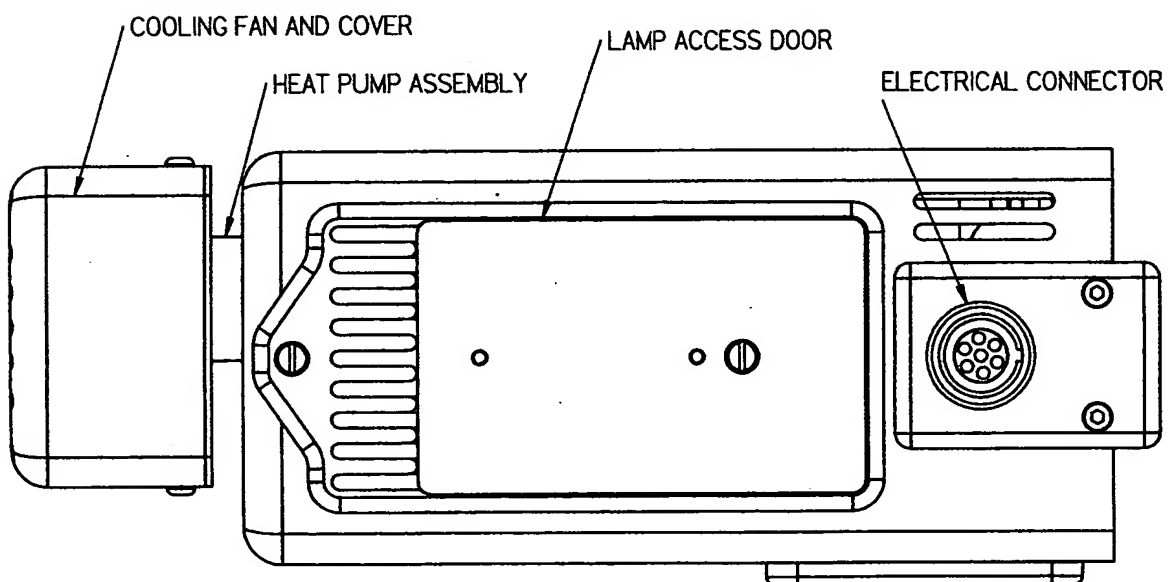


FIG. 11d

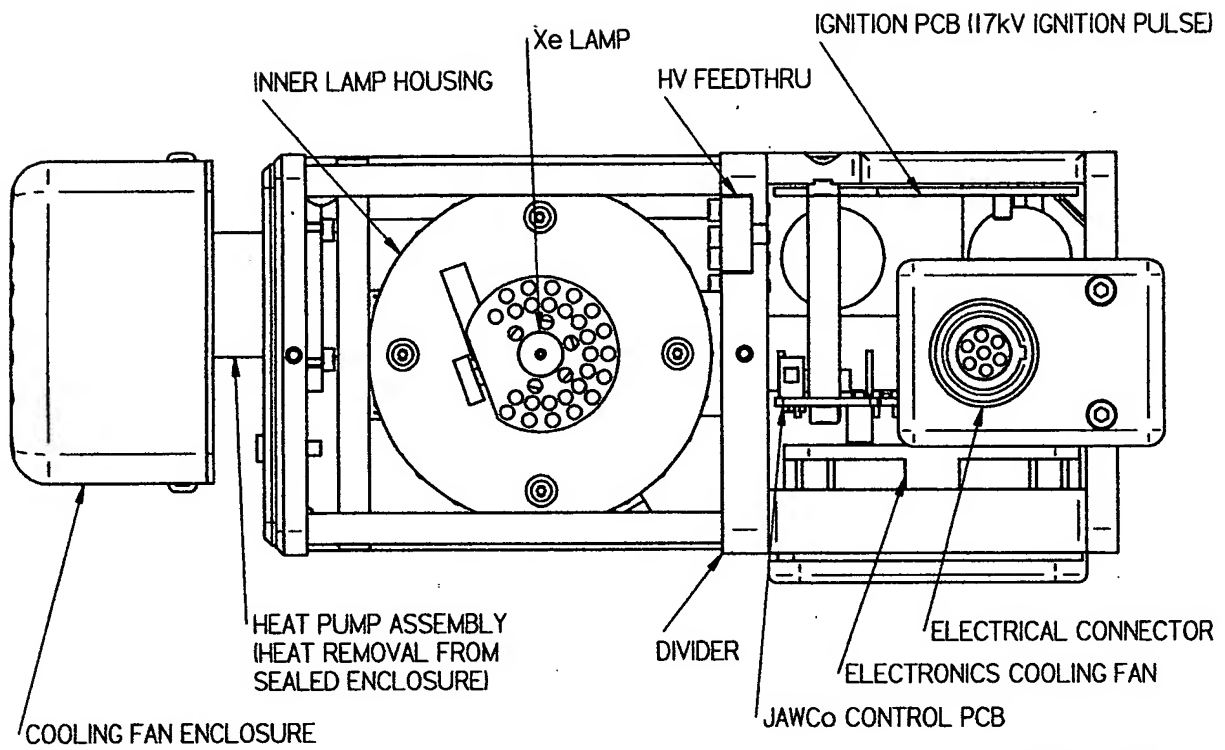


FIG. 11e

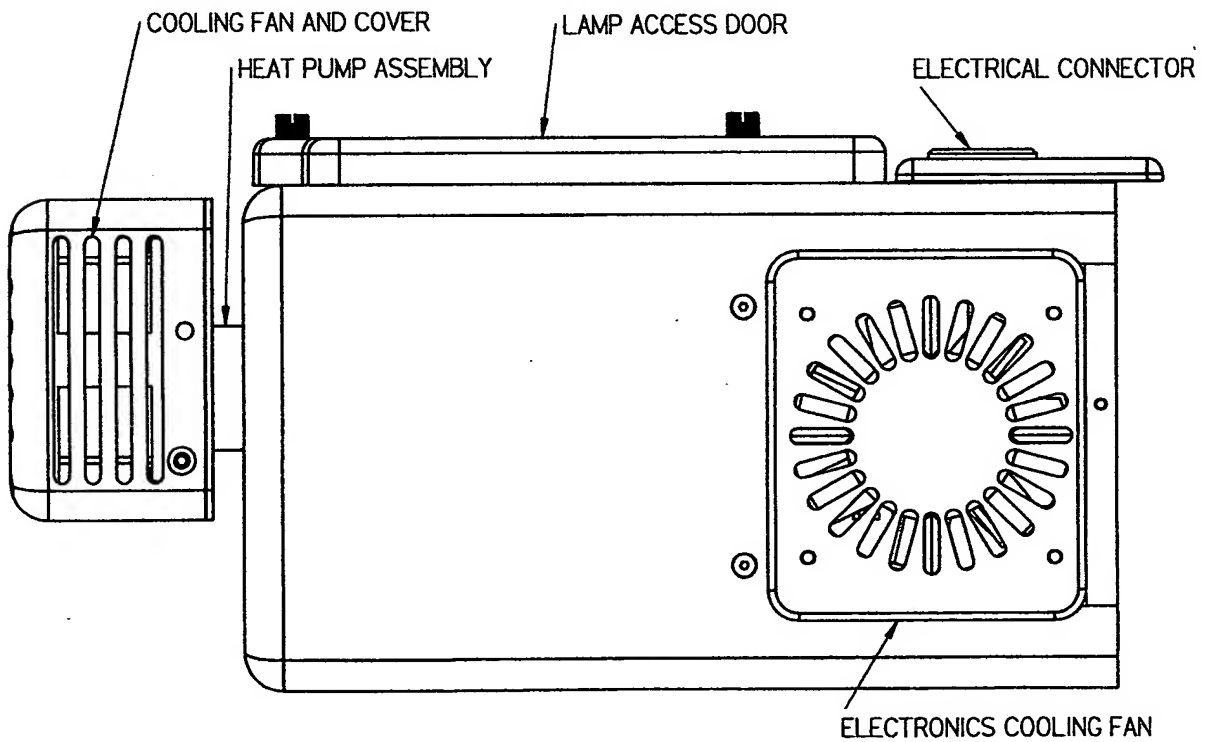


FIG. 11f